



SHEET 1 OF 2

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
055071-0328SERIAL NO.
10/756,829APPLICANT
Robert John SOCHA, et al.FILING DATE
January 14, 2004GROUP
2825

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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EXAMINER

/Suresh Memula/

DATE CONSIDERED

08/28/2007

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